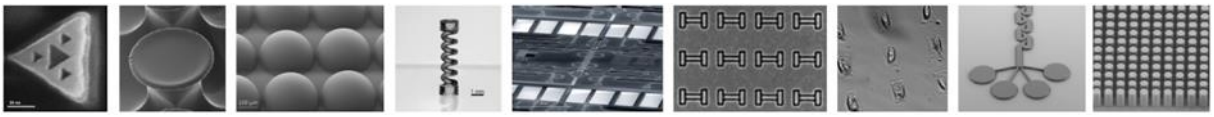


Symposium on Direct Write, Optical, Ion and Electron Beam Lithography
February, 18th – 19th

This symposium features technical experts and customers from Heidelberg Instruments, Nanoscribe, micro resist technology, GenISys and Raith who will describe the spectrum of latest, state-of-the-art direct-write capabilities.

Tuesday, 18.02.2020

11:30 – 12:30
Light Lunch and Welcome Reception

12:30 – 13:00
Welcome and Introduction
Harald Giessen,University of Stuttgart (4. Institute of Physics)

13:00 – 13:30
Advanced Nanofabrication for THz data transmission
Lothar Hahn, KIT (Karlsruhe Institute of Technology)

13:30 – 14:00
Quantum X: High-speed 2.5D microfabrication of refractive and diffractive microoptics
Alexander Legant, Nanoscribe GmbH

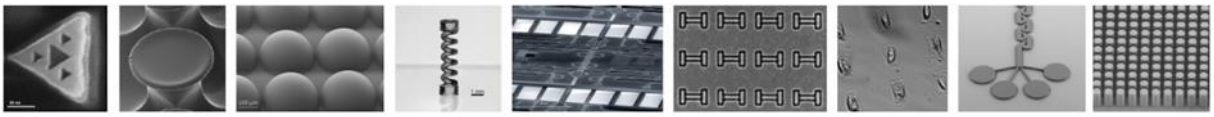
14:00 – 14:30
Coffee Break

14:30 – 15:00
3D greyscale lithography
Holger Sailer, IMS Chips (Institute of Microelectronics)

15:00 – 15:30
Update on Highlights in Resist & Photopolymer Development for UV direct writing and E-beam lithography
Anja Voigt, micro resist technology GmbH

15:30 – 16:00
Laser direct writing via HIMT VPG 400 - Developments and Applications
Angela Schneider - IMS Chips (Institute of Microelectronics)

16:00 – 18:30
Process Clinic (open discussion about process related challenges)



Wednesday, 19.02.2020

09:00 – 09:30
Direct Write Nano- and Microlithography Systems using Photons and Phonons
Felix Holzner, Heidelberg Instruments Nano

09:30 – 10:00
3D printed micro-optics: Millimeter size, multiple materials, and combining refractive and diffractive imaging leads to novel functionalities
Simon Thiele, University of Stuttgart (Institute of Applied Optics [ITO])

10:00 – 10:30
Process Simulation and Correction for 3D (greyscale) e-beam and laser lithography
Thomas Michels, Nezih Ünal, GenISys GmbH

10:30 – 11:00
Coffee Break

11:00 – 11:30
Turning randomly distributed 1D and 2D materials into functional devices
Frank Nouvertné, Raith GmbH

11:30 – 12:00
E-beam related work at MPL
Olga Lohse, Max Planck Institute for the Science of Light